

### Kirk Effect:-

- At high collector current the effective current gain ( $\beta$ ) drops.  
This phenomenon is known as kirk effect.

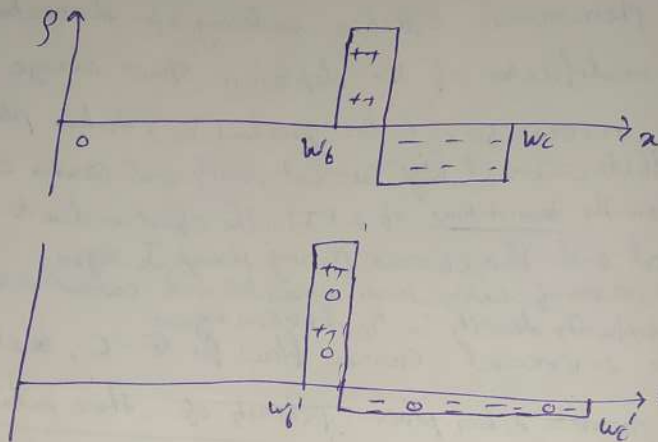
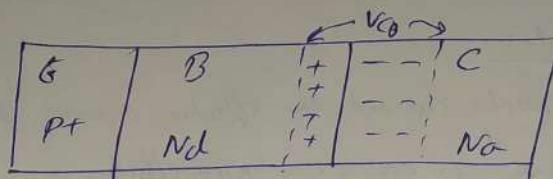
- In this phenomenon effective widening of the neutral base due to modification of the depletion space charge distribution at the reverse biased B-C junction ( $J_C$ ) takes place.

The kirk effects occur at high current density and causes a dramatic increase in the transit time of a BJT. The effect is due to charge density associated with the current passing through  $J_C$  region. This effect occurs if charge density associated with current is larger than the ionised impurity density in  $J_C$  depletion region.

- Due to increased current flow for E-C, buildup of mobile carriers takes place. Polarity of these mobile charges adds to fixed donor charges on the base side of B-C depletion region and subtracts from the fixed acceptor charges on the collector side of junction.

- Hence, fewer uncompensated donors (smaller depletion width) are needed to maintain reverse bias  $V_{CB}$  across the junction. Also due to that neutral base width increases.

- Due to this phenomenon effective widening of the neutral base region in collector region takes place. Also a drop of current gain and increase of base transit time take place.



- (a) Cross section of PNP BJT
- (b) Space charge distribution in IC reverse biases for very low current.
- (c) Space charge distribution in IC reverse bias for light current.

The electric field at IC from Poisson's eqn is given by.

$$\frac{dE}{dx} = \frac{1}{\epsilon} \left[ q(N_A^+ - N_D^-) + \frac{I_C}{A v_d k} \right] \text{ drift vel.}$$

↑ mobile carrier charge concentration

$V_{CB} \approx E$

$V_{CB} = -$

- Assum

- In pos region has

low end

- The levels to +

$V_{CB}$  & Electric field  $E$  is related by.

$$V_{CB} = - \int_{w_b}^{w_c} E dx$$

- Assuming  $V_{CB}$  ~~is fixed~~ is fixed and  $I_C$  increases.
- In Poisson's eqn the extra holes injected into the depletion region have some effect if doping level on base side were increased and that on collector side decreased.
- The base widening can extend at even higher current levels all the way through the lightly doped collector region to the heavily doped buried sub-collector.



Basic requirement of high Freq<sup>n</sup> Transistor are as below

- Physical size should be small.
- Base width must be narrow to reduce transit time.
- Emitter and collector areas must be small to reduce junction capacitance.
- Effective resistance associated with each region should be min<sup>m</sup>, so that RC charging time should be min<sup>m</sup>.

A trade off bet<sup>n</sup> Power and Size is present for high freq<sup>n</sup> transistor.

Method of interdigitisation provides a means of increasing the useful emitter edge length while keeping overall area to a minimum.

To minimise the effective distance between E, B & C, hence RC time will be effected accordingly.

- Reduction of base resistance by heavy doping of the base requires the use of a heterojunction to maintain  $\gamma$  at an acceptable value.
- Collector depletion region must be kept as small as possible to reduce transit time of carriers drifting through collector junc<sup>n</sup>. This can be accomplished by making lightly doped collector region narrower.
- The packaging of transistor should be perfect to reduce the parasitic resistance, inductance or capacitance at high freq<sup>n</sup>.